

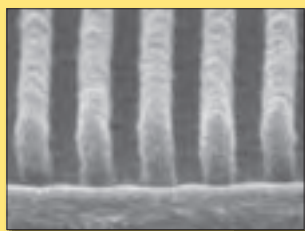
Revolutionary

Pushing Litho to the Limits

Topcoat-compatible ArF Resist

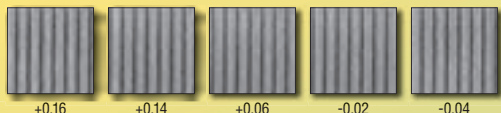
- Low LWR and excellent circularity
- Wide process latitude
- 37 nm line/space resolution

EPIC™ 2096 Photoresist



40 nm/80 nm Lines/Spaces at 1,100Å FT with 900Å OC™2000 Topcoat

37 nm/74 nm Lines/Spaces



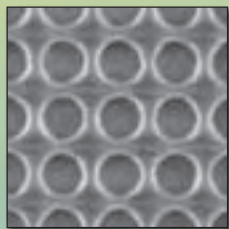
LWR = 3.6 nm; 45.0 mJ/cm²

40 nm/80 nm Lines/Spaces



LWR = 3.1 nm; 28.0 mJ/cm²

EPIC 2390 Photoresist

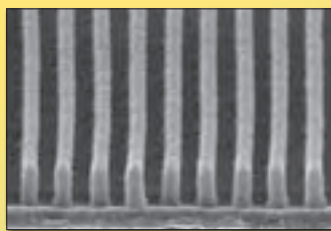


65 nm/130 nm Pitch Contact Holes, 180 nm FT

Embedded Barrier Layer Resist

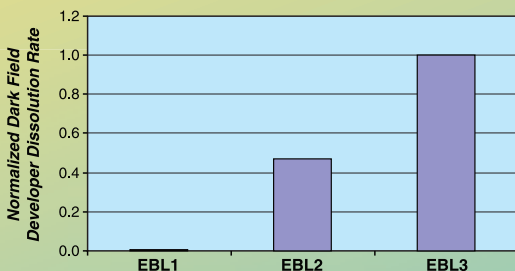
- LWR <4 nm at 42 nm lines/spaces
- EBL resists with RCA >75°
- Superb defect performance

EPIC iM5020 Photoresist



45 nm Lines/Spaces
25 nm AR™24 Anti-Reflectant

EBL Dissolution Rate Improvement



EBL Defect Level Improvement

